

# Deposition of CsSnI<sub>3</sub> perovskite thin films by Atomic Layer Deposition and pulsed Chemical Vapor Deposition

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## Supplemental Document

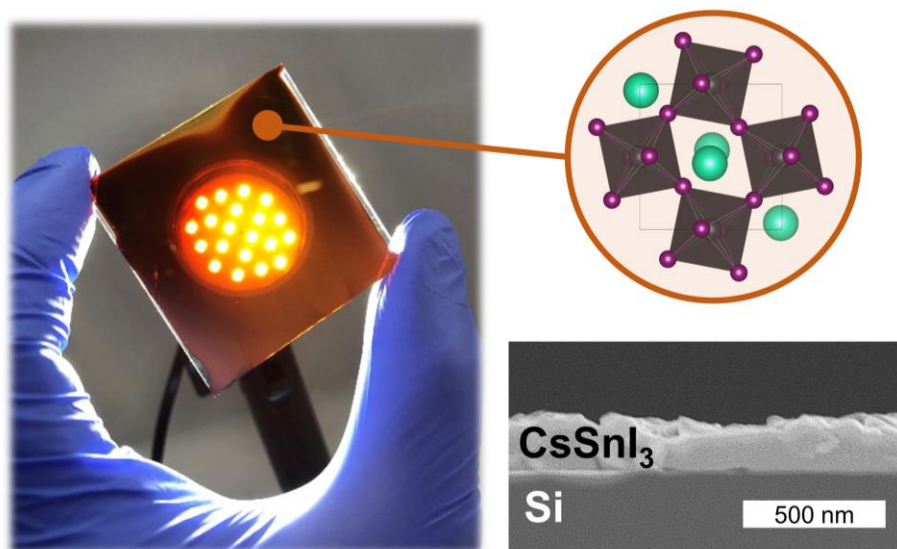


Figure 1: Left: Photograph of a CsSnI<sub>3</sub> film on a soda lime glass substrate, illuminated from the back. Right bottom: Cross-sectional SEM micrograph of a CsSnI<sub>3</sub> film on a silicon substrate.

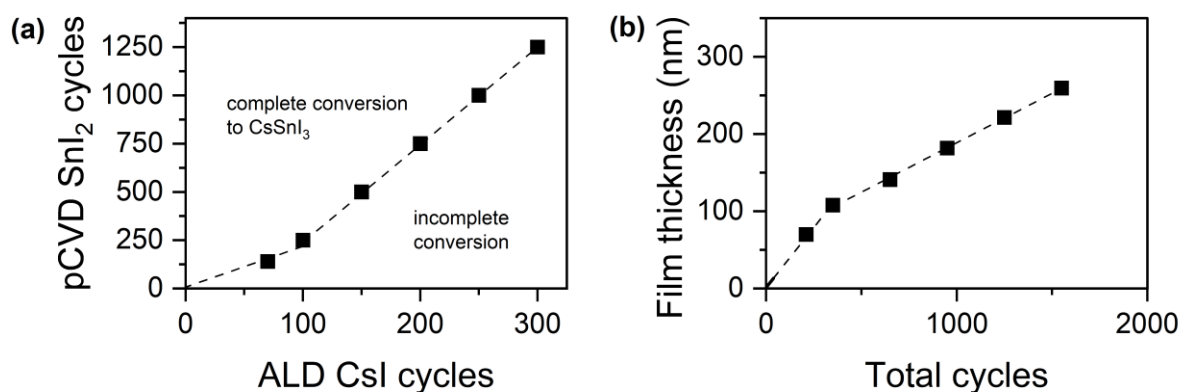


Figure 2: a) The lowest number of SnI<sub>2</sub> pCVD cycles needed to fully convert ALD CsI deposited with different cycle numbers. b) Film thickness as a function of the total number of ALD CsI and pCVD SnI<sub>2</sub> deposition cycles.